| Session Title: | [WC2] Advanced Cleaning Technology |
|---|---|
| Session Date: | November 22 (Wed.), 2023 |
| Session Time: | 10:20-11:30 |
| Session Room: | Room C (Grand Ballroom 2, 2F) |
| Session Chair: | Prof. Jinsub Park (Hanyang Univ., Korea) |

[WC2-1] [Invited] 10:20-10:50

**New Cleaning and Etch Solution Approaches for Advanced sub 5nm Technology Nodes**

Andreas Klipp, Haci Osman Guevenc, and Francisco Javier Lopez Villanueva (BASF SE, Germany)

[WC2-2] [Invited] 10:50-11:10

**BOE-Based High Selective $SiO_2$ Etching Technology Applicable to Next-Generation Semiconductor Manufacturing Process**

Myung Ho Lee, Bun Sung Jung, Hak Soo Kim, and Myung Geun Song (ENF Tech. Co., Ltd., Korea)

[WC2-3] 11:10-11:30

**Fenton Reaction for Enhancing Ag-Film Polishing-Rate in Chemical-Mechanical-Planarization**

Man-Hyup Han (Hanyang Univ., Korea), Jin-Hyung Park (ENF Tech. Inc., Korea), and Jae-Gun Park (Hanyang Univ., Korea)